

Analysis of Impurities in o-xylene using Agilent J&W FactorFour VF-WAXms GC Columns

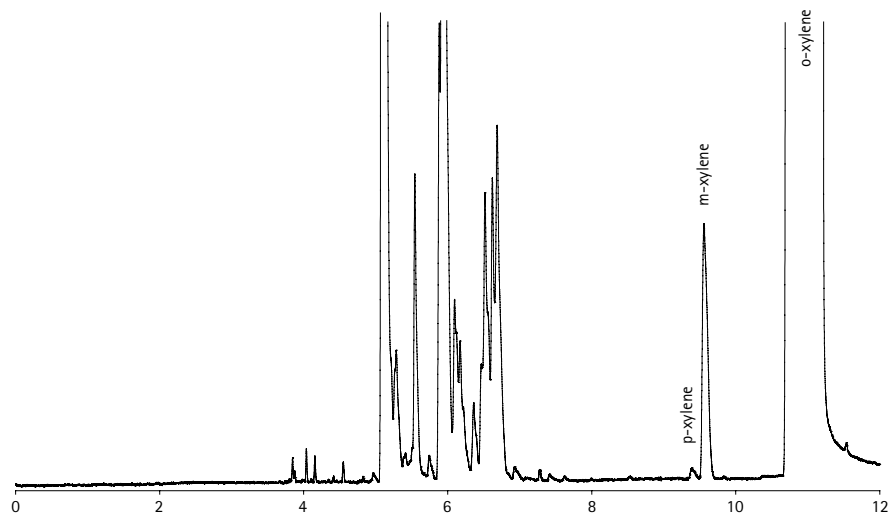
Application Note

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Conditions

Technique:	GC-FID	Injector:	250 °C, split 75 mL/min
Column:	VF-WAXms 60 m x 0.25 mm df = 0.25 µm (p/n CP9207)	Detector:	275 °C, FID
Temperature:	55 °C to 150 °C with 4 °C/min	Sample Size:	0.1 µL
Carrier Gas:	Helium, 2.0 bar	Sample:	o-xylene



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